

U-MAX (UPE)



Descriptions

- CSM U-max use Ultra-high molecular weight Polyethylene (UPE) Membranes, with the highest particle retention efficiency required by photoresist process.

Application

- Electronics : Photoresist chemical filtration
- Chemicals : Ultrapure solvent filtration

Materials

Media	Ultra high molecular weight Polyethylene (UPE)
Support/Drainage	High Density Polyethylene (HDPE)
Core/Cage	High Density Polyethylene (HDPE)
O-ring	TEV*

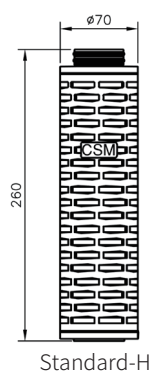
* Viton and Teflon are trademarks of DuPont

Specifications

Type	H		
Removal Range	5nm	10 / 20nm	50~200nm
Membrane Area	1.3m ²	1.2m ²	1.1m ²
Length [inch]	10 / 20		
Max. Temperature	60°C		
Max. Differential Pressure	0.3MPa@25°C		

* If you need further information on specification, please contact us

Dimensions



End Cap Options

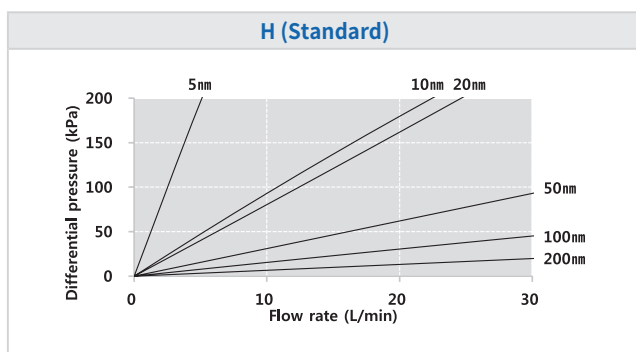


M

U-MAX (UPE)

UP (UPE Membrane)

Pressure Drop vs Flow Rate (10" cartridge filter, Water 20°C)



Metal Ion Extraction Test

Solvent	Li	Na	Mg	Al	K	Ca	Cr	Mn	Fe	Ni	Cu	Zn	Ag	Cd	Sn	Ba	Pb
PGMEA ¹⁾	<1	<2	<1	<1	<2	<2	<1	<1	<1	<2	<1	<1	<1	<1	<2	<1	<2
PGME ²⁾	<1	<1	<1	<1	<2	<2	<1	<1	<1	<1	<1	<1	<1	<1	<1	<1	<1
NMP ³⁾	<1	<1	<1	<1	<1	<1	<1	<1	<1	<1	<1	<1	<1	<1	<1	<1	<1

※ Test term : 7 days soaking

※ Measuring equipment : ICP-MS

1) PGMEA : Propylene glycol monomethyl ether acetate

2) PGME : Propylene glycol monomethyl ether

3) NMP : N-Methylpyrrolidone

Ordering Information

H (Standard)

1 HUPE 2 3 4 5 6

No. 1

Code	Grade
E	Electronic

No. 2

Code	Micron Rating
N5	5nm
A1	10nm
A2	20nm
A5	50nm
01	100nm
02	200nm

No. 3

Code	End Cap
M	222 O-ring / Flat

No. 4

Code	Length
1	10"
2	20"

No. 6

Code	Special Option
C	UPW Cleaning

No. 5

Code	O-ring
T	TEV